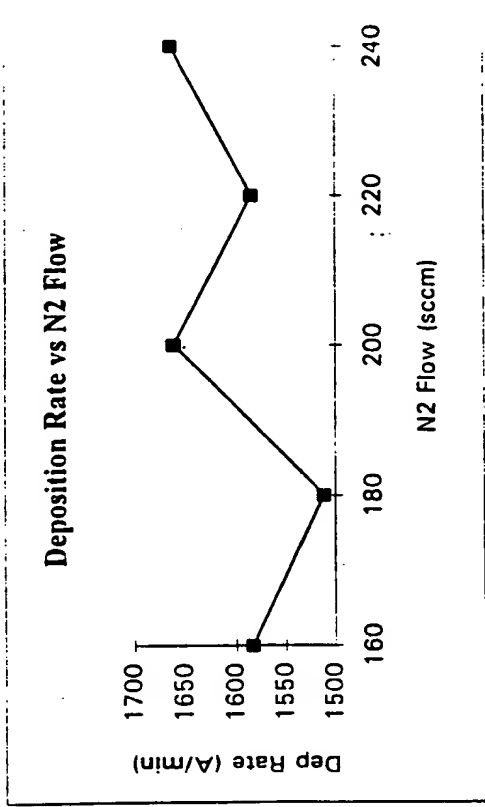
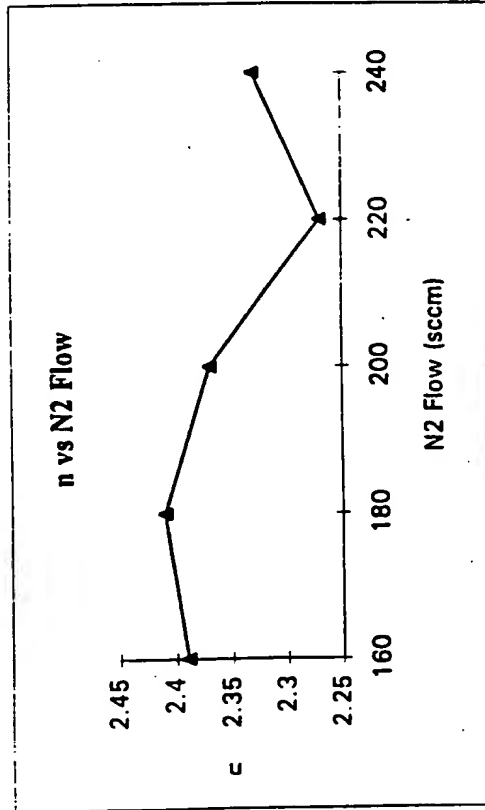
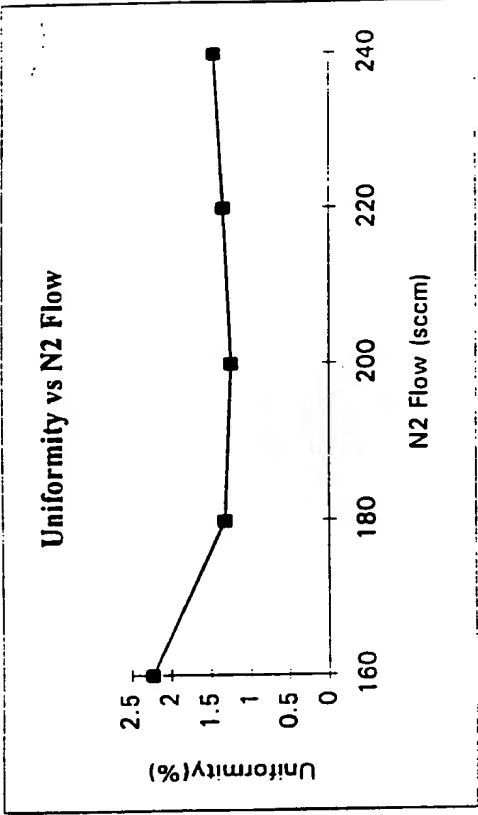
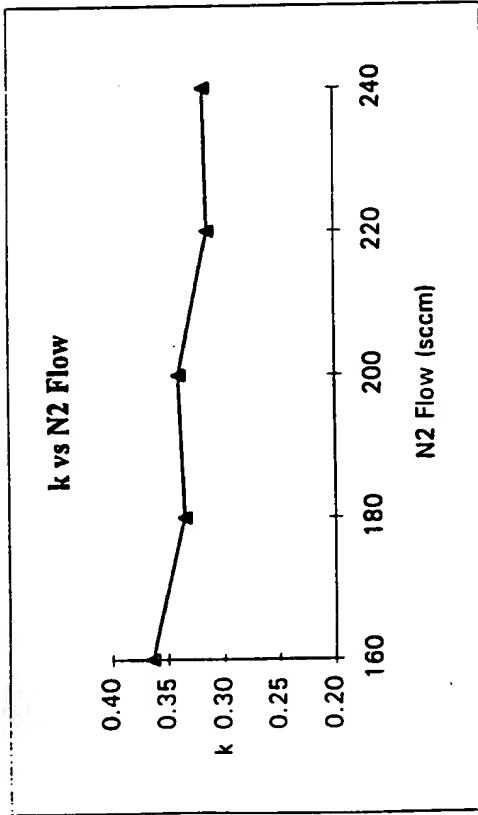
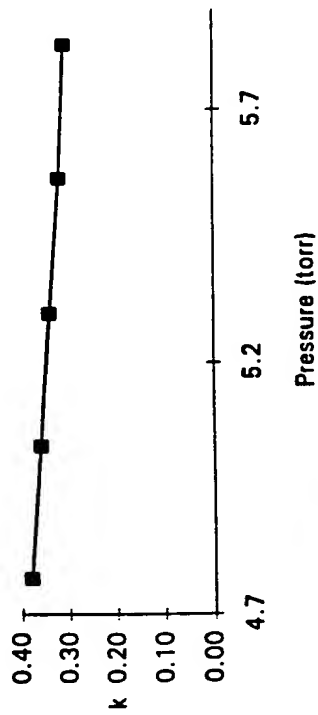


200mm ARL Process Trends (300A/356nm)

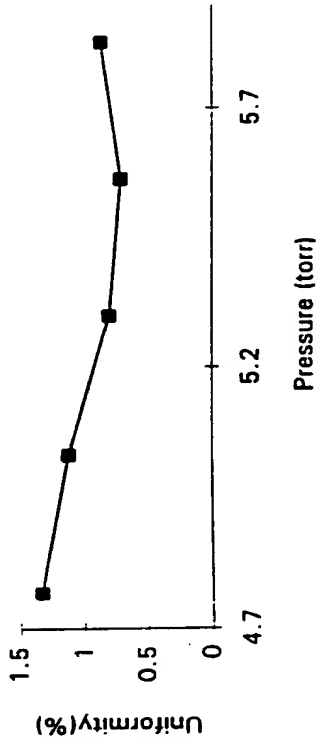


200mm ARL Process Trends (300A/356nm)

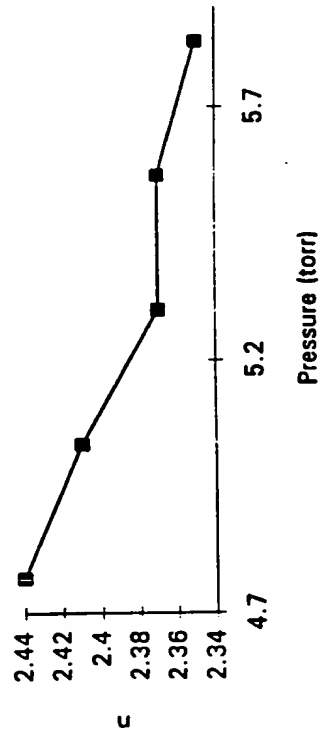
k vs Pressure



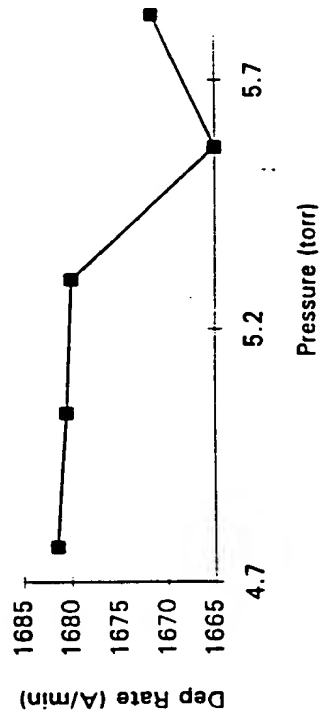
Uniformity vs Pressure



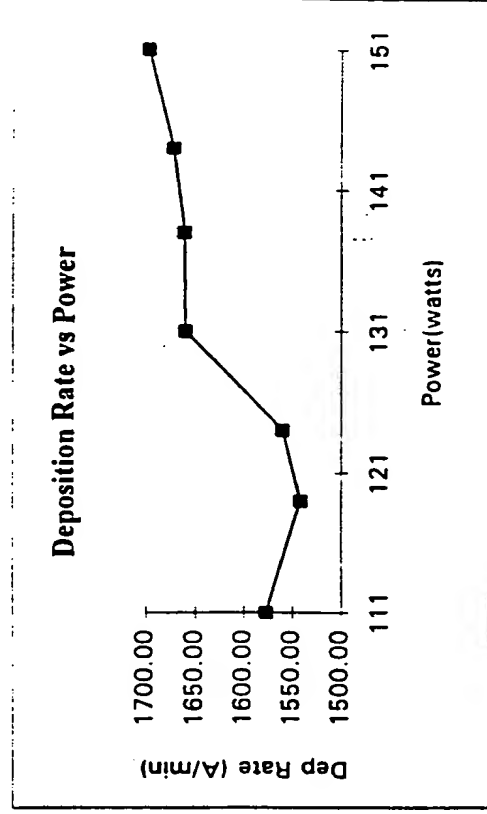
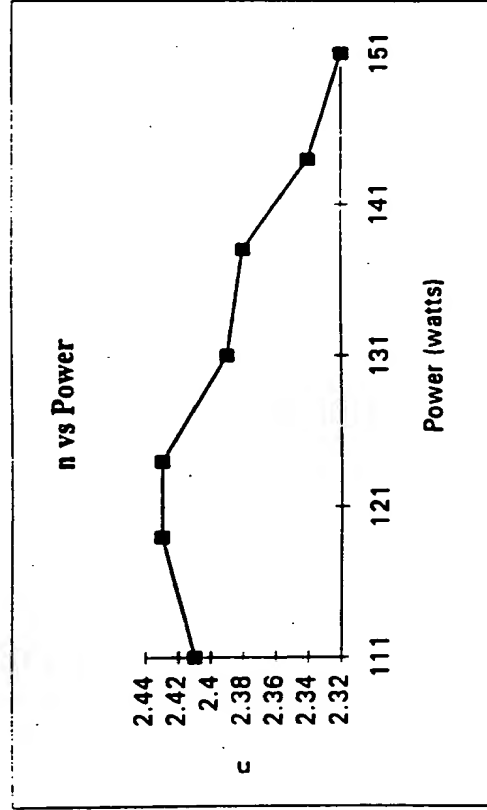
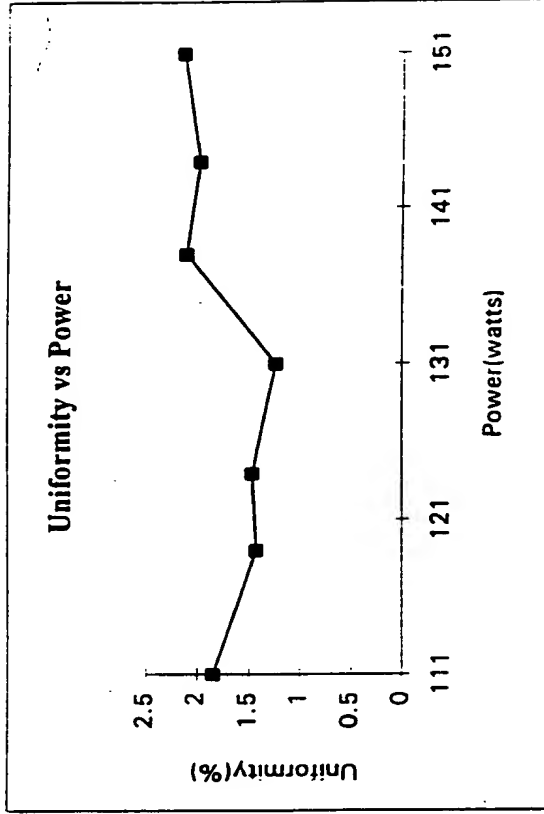
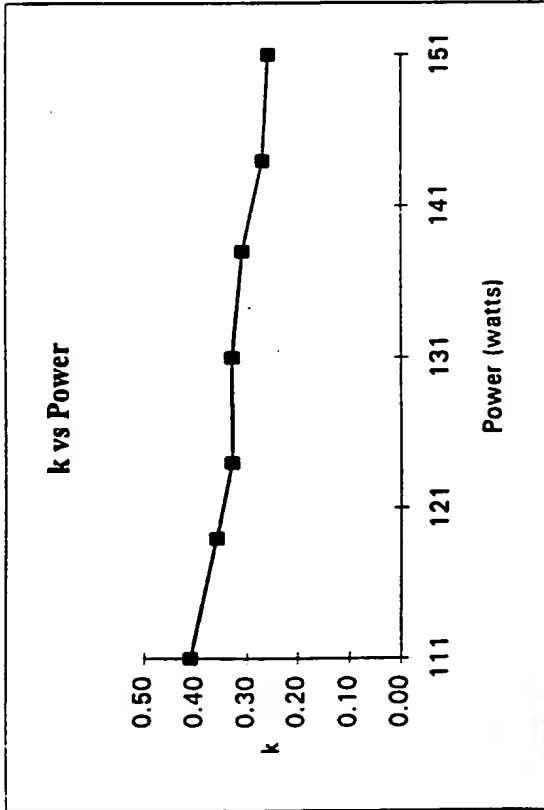
n vs Pressure



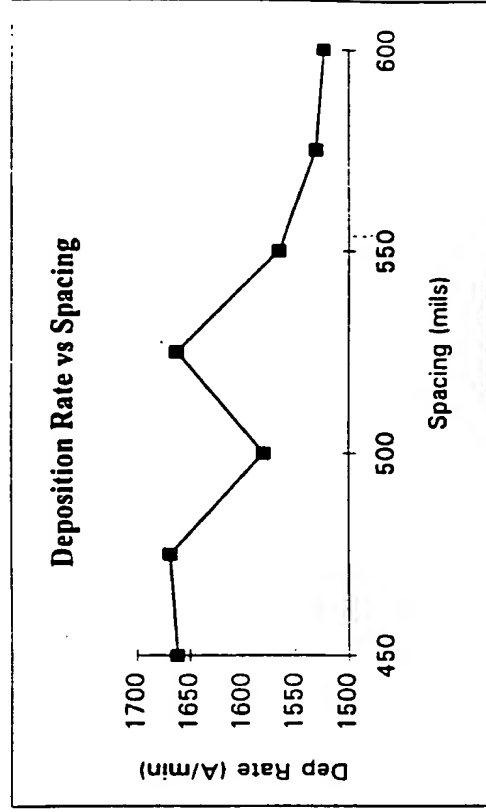
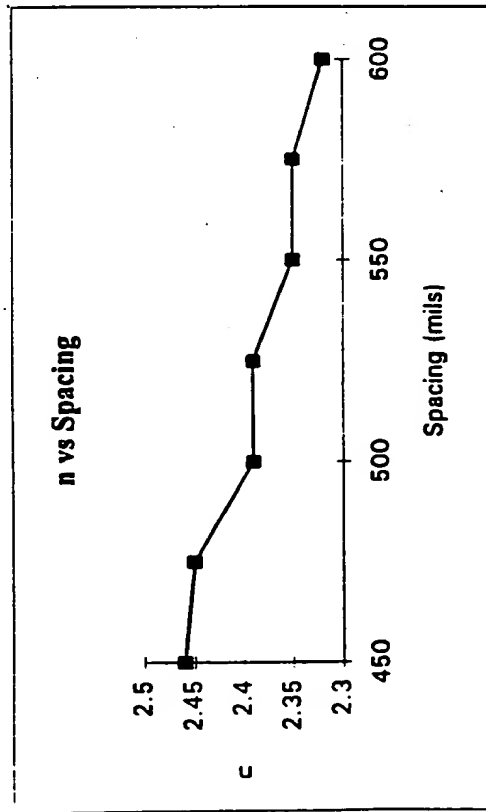
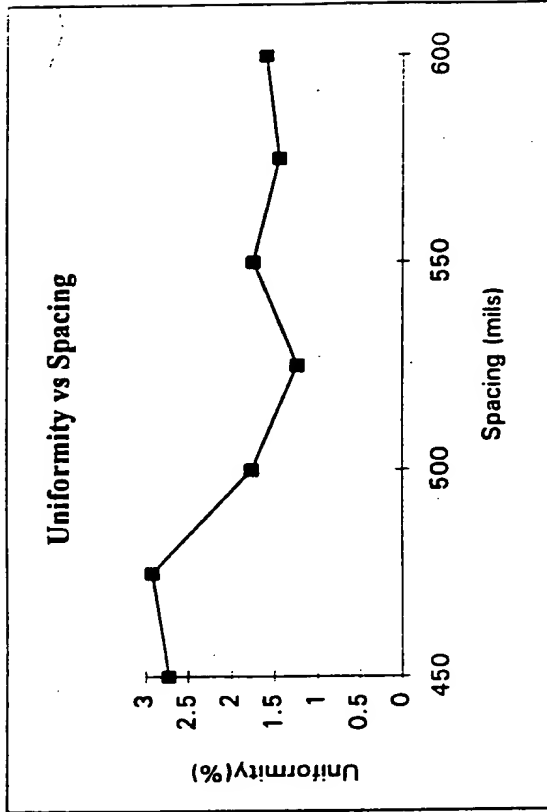
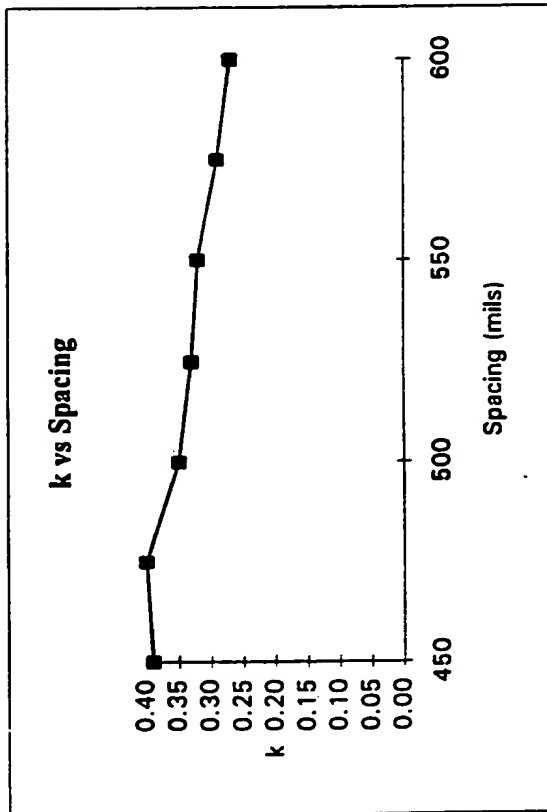
Deposition Rate vs Pressure



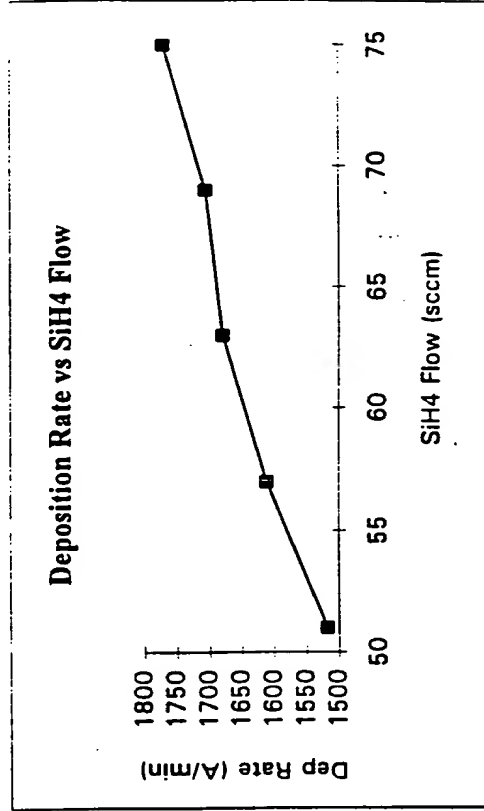
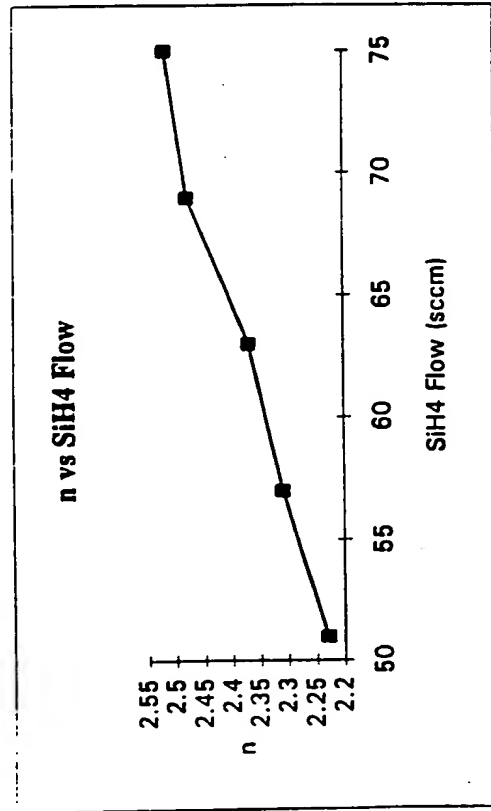
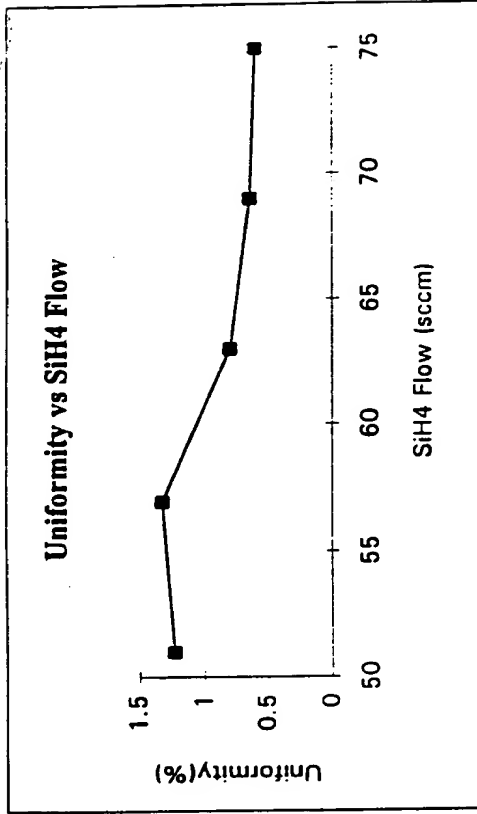
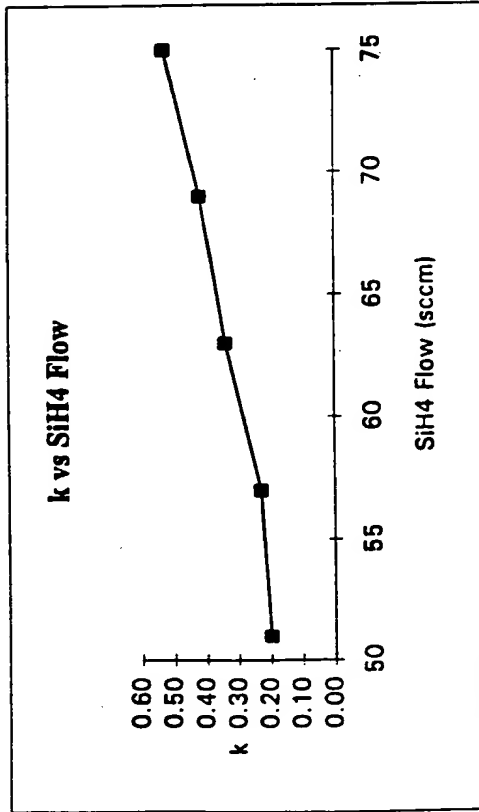
200mm ARL Process Trends (300A/356nm)



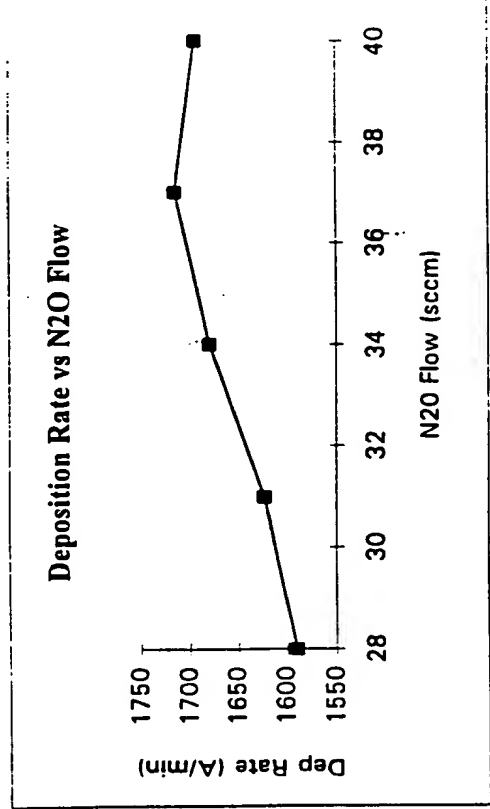
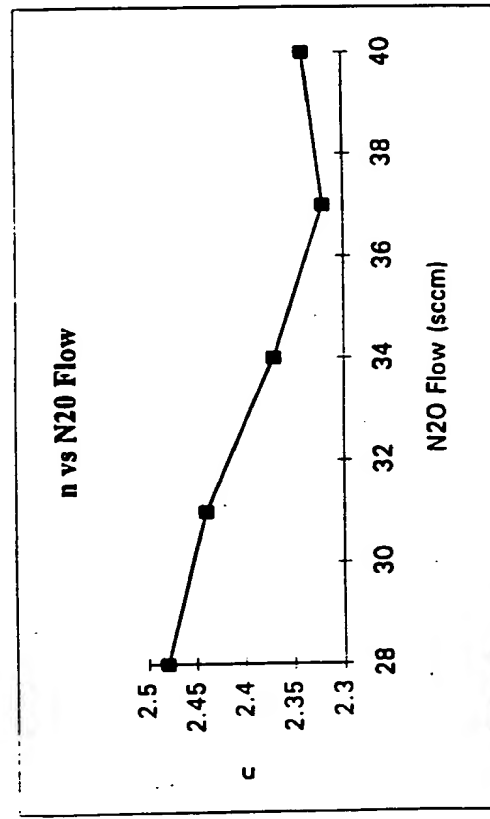
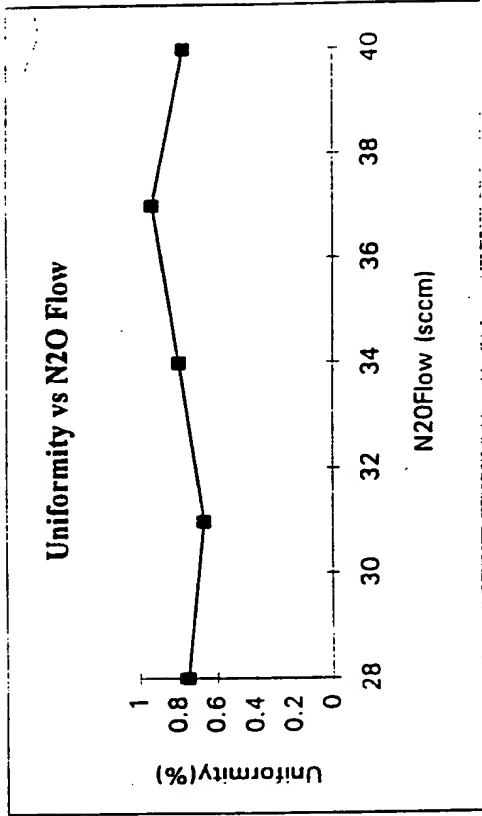
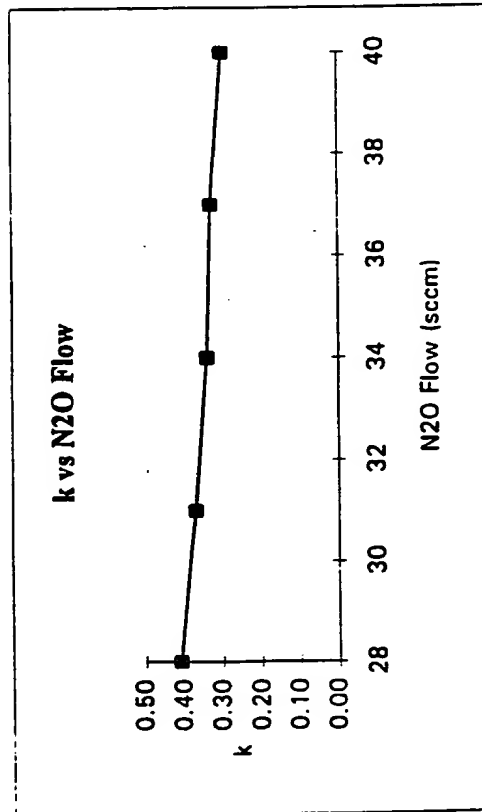
200mm ARL Process Trends (300A/356nm)



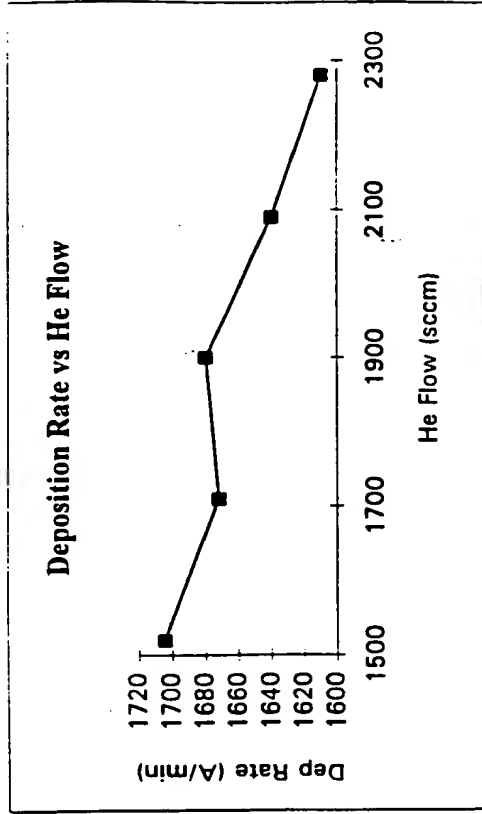
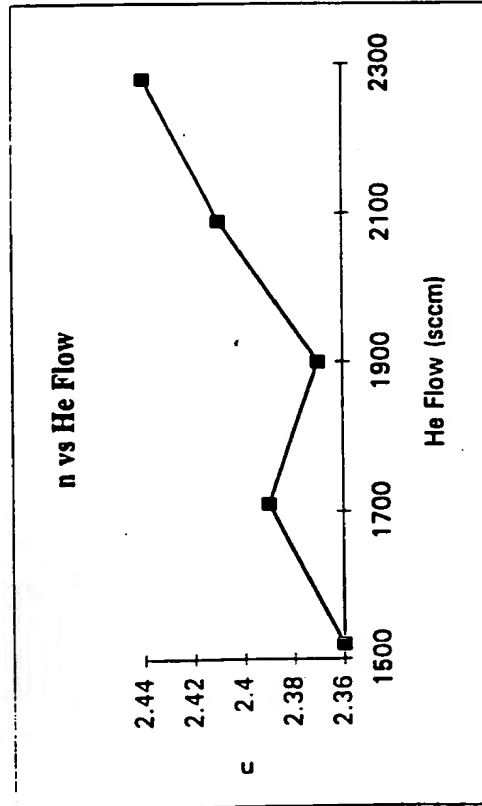
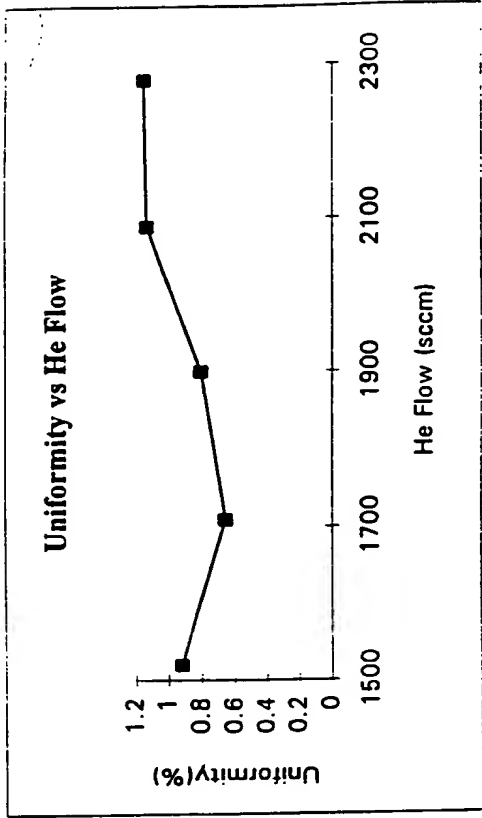
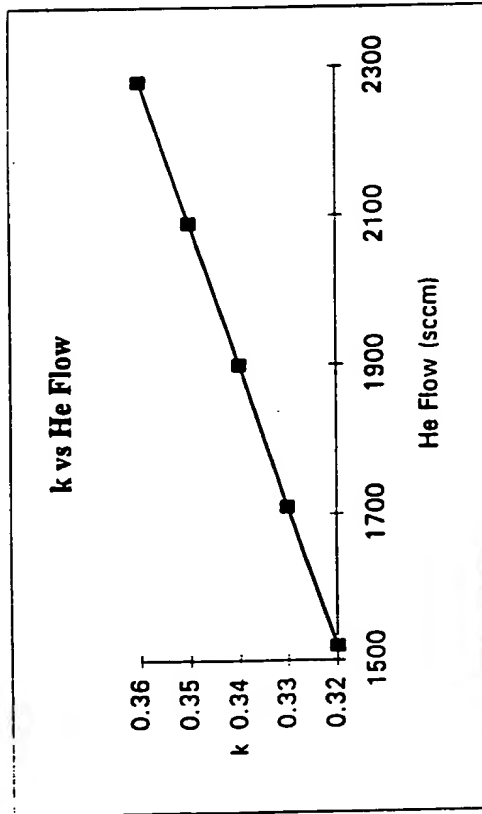
200mm ARL Process Trends (300A/356nm)



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